

23251

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau



16 MAR 2005



(43) International Publication Date
25 March 2004 (25.03.2004)

PCT

(10) International Publication Number
WO 2004/025367 A2

(51) International Patent Classification⁷: **G03F 7/00**

BISCARINI, Fabio [IT/IT]; Via Umberto Brunelli, 4,
I-40135 Bologna (IT).

(21) International Application Number:
PCT/EP2003/010242

(74) Agent: **MODIANO, Guido**; Modiano & Associati, Via
Meravigli, 16, I-20123 Milano (IT).

(22) International Filing Date:
15 September 2003 (15.09.2003)

(81) Designated States (*national*): AE, AG, AL, AM, AT, AU,
AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU,
CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE,
GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR,
KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK,
MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT,
RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR,
TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
MI2002A001961
16 September 2002 (16.09.2002) IT

(84) Designated States (*regional*): ARIPO patent (GH, GM,
KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW),
Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),
European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE,
ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO,
SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM,
GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

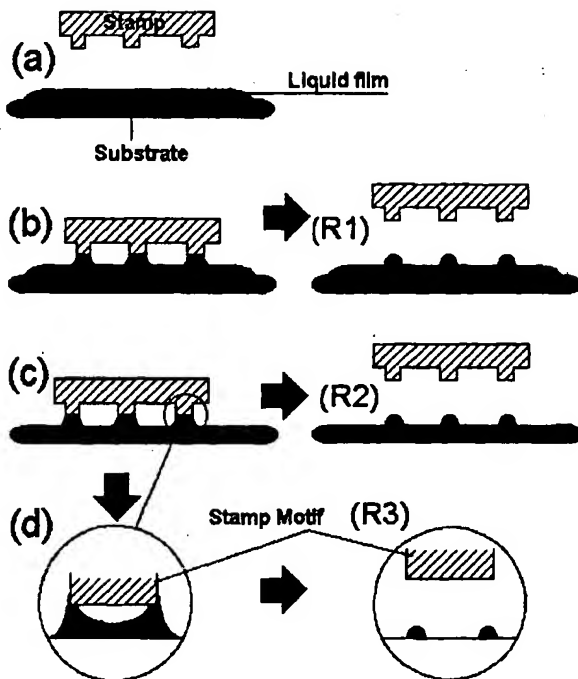
(71) Applicant (*for all designated States except US*): **CON-
SIGLIO NAZIONALE DELLE RICERCHE** [IT/IT];
Piazzale Aldo Moro, 7, I-00185 Roma (IT).

(72) Inventors; and

(75) Inventors/Applicants (*for US only*): **CAVALLINI, Mas-
similiano** [IT/IT]; Via Lucca, 62, I-40038 Vergato (IT).

[Continued on next page]

(54) Title: METHOD FOR MANUFACTURING AND CONTROLLING STRUCTURES AND PATTERNS OF SOLUBLE AND COLLOIDAL SUBSTANCES BY PRINTING ON THE MICROMETER AND NANOMETER SCALE AND WITH REDUCTION OF THE DIMENSIONS OF THE STAMP'S FEATURES



(57) Abstract: A printing process for obtaining patterns of nanometer and micrometer dimensions on a substrate, comprising i) the application of a solution or suspension of an imprinting material to the substrate, ii) the positioning, without applying pressure, of a stamp provided with relief patterns at a distance of 0 nm to 500 μ m from the substrate, and iii) the evaporation of the solution or suspension.

WO 2004/025367 A2